

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1312	capacitor and (electrode and (cvD or ALD or (chemical adj vapor adj deposition) or (atomic adj layer adj deposition)) same (Ta2O5 or tantalum))	USPAT	ADJ	ON	2005/06/09 12:41
L2	1089	capacitor and (electrode and (cvD or ALD or (chemical adj vapor adj deposition) or (atomic adj layer adj deposition)) same (Ta2O5 or tantalum))	US-PGPUB	ADJ	ON	2005/06/09 12:41
L3	1	capacitor and (electrode and (cvD or ALD or (chemical adj vapor adj deposition) or (atomic adj layer adj deposition)) same (Ta2O5 or tantalum))	EPO	ADJ	ON	2005/06/09 12:42
L4	27	capacitor and (electrode and (cvD or ALD or (chemical adj vapor adj deposition) or (atomic adj layer adj deposition)) same (Ta2O5 or tantalum))	JPO	ADJ	ON	2005/06/09 12:43
L5	46	capacitor and (electrode and (cvD or ALD or (chemical adj vapor adj deposition) or (atomic adj layer adj deposition)) same (Ta2O5 or tantalum))	DERWENT	ADJ	ON	2005/06/09 12:43
L6	1	capacitor and (electrode and (cvD or ALD or (chemical adj vapor adj deposition) or (atomic adj layer adj deposition)) same (Ta2O5 or tantalum))	IBM_TDB	ADJ	ON	2005/06/09 12:43